

ABSTRACT OF THE DISCLOSURE

--In a method of fabricating a thin film transistor array substrate, a black matrix having separated portions is first formed on a substrate with an opaque conductive material. An insulation layer is formed to cover the black matrix. A gate line assembly and a data line assembly are formed over the black matrix and insulation layer. Buffer layers are formed to cover the gaps between the separate portions of the black matrix. The buffer conductive layers are formed at the same plane as the gate line assembly or data line assembly.--

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